



AP/IRW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Koji NOZAKI et al.**

Group Art Unit: **1752**

Serial No.: **10/623,679**

Examiner: **Amanda C. Walke**

Filed: **July 22, 2003**

Confirmation No.: **5083**

For: **RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN
AND PROCESS FOR FORMING THE SAME, AND SEMICONDUCTOR
DEVICE AND PROCESS FOR MANUFACTURING THE SAME**

Attorney Docket Number: **030891**

Customer Number: **38834**

RESPONSE AFTER FINAL

BOX: AF

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

Date: April 7, 2005

Sir:

In response to the Office Action dated January 25, 2005, Applicants argue as follows:

Remarks begin on page 2 of this paper.